

# [MASK FOR FABRICATING A CONTACT AND CONTACT PROCESS THEREOF]

## Abstract

A mask for fabricating contacts is provided. The mask has a contact pattern with an edge pattern around the edge of the contact pattern. The edge pattern is a half-tone region. Due to the half-tone edge pattern on the mask, contact angle between the side-wall of the contact opening and an underlying conductive layer after a patterning process is reduced.